

- Robust design and ease of operation
- Focussing mirror for small spot
- Low operating pressure (10⁻¹¹ mbar range)
- He I / He II monochromator
- NEW: Ar-I α radiation monochromator



HIS 13

HIGH INTENSITY VUV SOURCE **BASE UNIT**



- Ease of operation
- Robust design

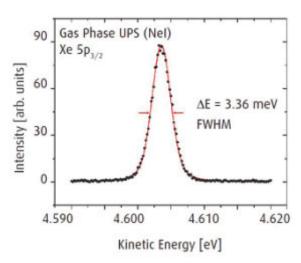
Discharge regulation

The VUV source power supply with up to 300 mA discharge current, integrated pressure gauge display and fast electronic ignition supports ease of operation and optimized source brightness.

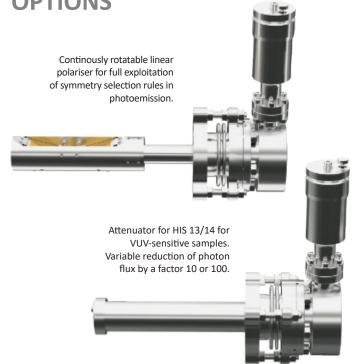
Ease of operation, robust design and a high intensity make the HIS-series the preferred excitation sources for UPS. The source is available with multiple options such as a linear polarizer, 3rd differential pumping stage, focusing mirror for small spot, an attenuator to tune light intensity and a He I and He II monochromator. All options/upgrades can be retrofitted.

More than 350 installed units stand for reliable quality.





The line width of the gas phase spectrum is dominated by the Xe Doppler broadening and the analyser resolution. It proves a line width less than 2 meV of the HIS 13 operated with Ne.

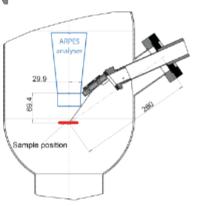


FOCUSED VUV SOURCE

- Designed for μ-ARPES and Momentum Microscopy (e.g. NanoESCA MARIS)
 - Small spot down to < 180 μm FWHM
 - Flux > 10¹³ photons/s/mm²



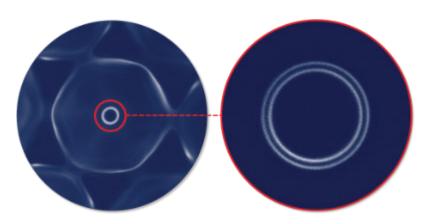
The HIS 14 HD can be installed on a dedicated flange (new systems) or retrofitted to an existing chamber with a flange NW 63 CF or larger. FOCUS will provide the corresponding customized adapter. Please contact us for individual clarification.



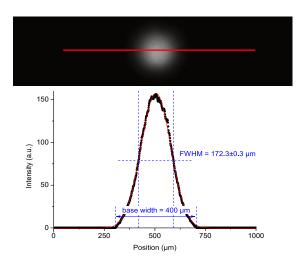
The HIS 14 HD fine focused VUV-lamp is the ideal photon laboratory source for ARPES and PEEM with < 180 μ m spot size, ca. 70 mm working distance (170 mm optional).

The flux density is 50 x higher compared to a non-focused source. A 3rd pumping stage allows for operation in the low 10⁻¹⁰ mbar range.

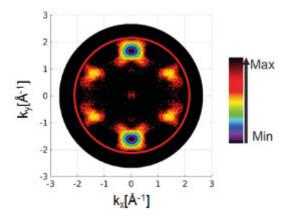
The source is mounted an a CF 63 ID or CF 100 ID flange.



Au (111) Rashba split surface state measured with HIS 14 HD using He I excitation, measured with the NanoESCA MARIS momentum microscope.



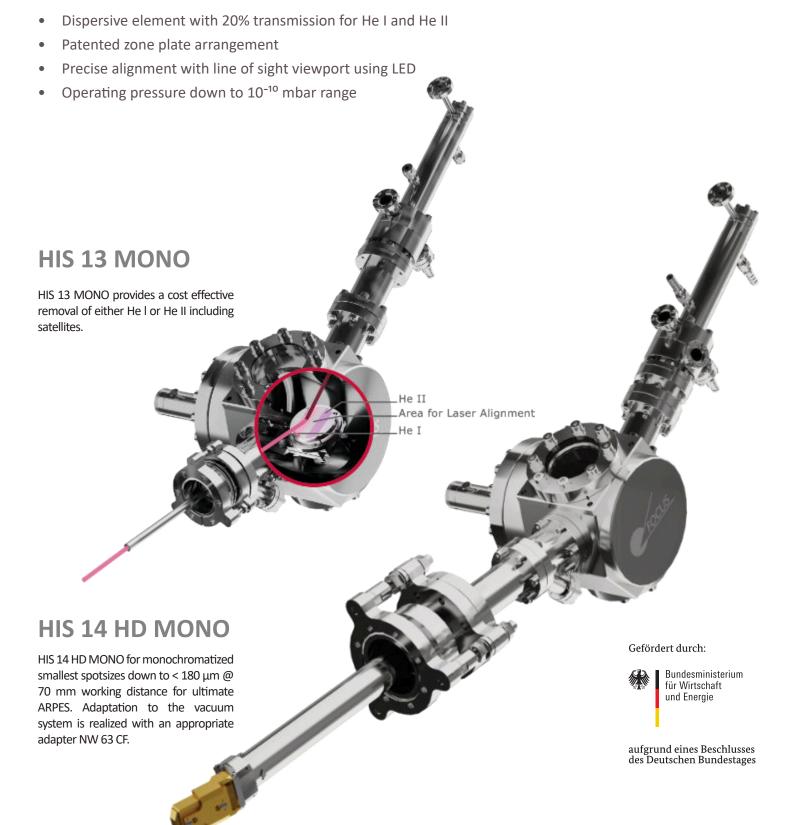
Beam spot profile of HIS 14 HD with <180 μ m FWHM.



 k_{y} - k_{y} map of the HOMO of NTCDA on Cu (111)

Dwell time 45 min Courtesy: Prof. Christian Kumpf, FZ Jülich GmbH, PGI-3

VUV MONOCHROMATOR FOR HIS SERIES

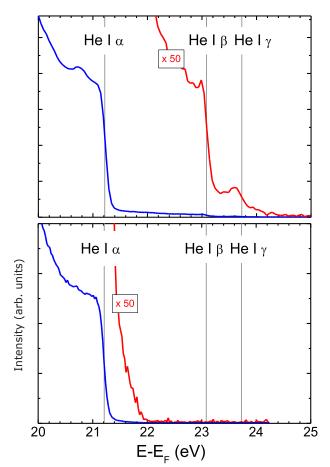


The working principle of the monochromator is based on a reflection zone plate which separates the different wavelengths via diffraction in a patented design. The zone plate provides > 20% transmission for He I and He II. With a linear motion drive each of 3 different zone plate areas can be positioned in the beam path for monochromated He I and He II illumination or for simple optical alignment.

The unique optical alignment with a laser (included) uses the view port at the rear of the source and hence allows to control the full lenght of the optical path up to the spot position on the sample.

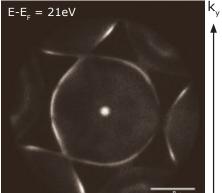


Momentum microscopy of Ag (111) using FOCUS IEF-PEEM



 $E-E_{F} = 21eV$ $\frac{1 \text{ Å}^{-1}}{1 \text{ Å}^{-1}}$

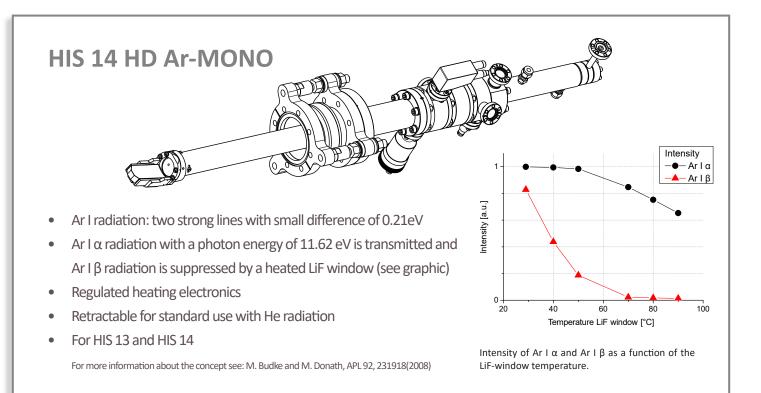
Without Monochromator



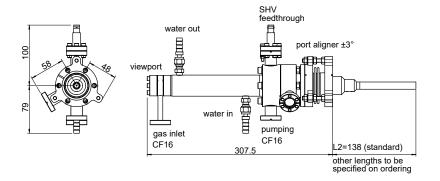
With Monochromator

Top: Satellites He I- β and γ present Bottom: No satellites

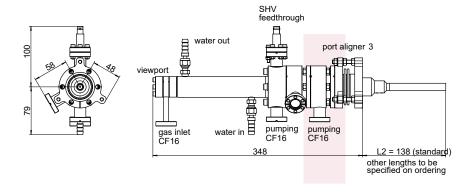
Top: Shadow-structure visible due to He I- β Bottom: Band-structure due to He I- α solely



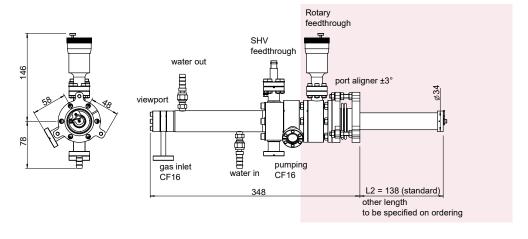
TECHNICAL INFORMATION



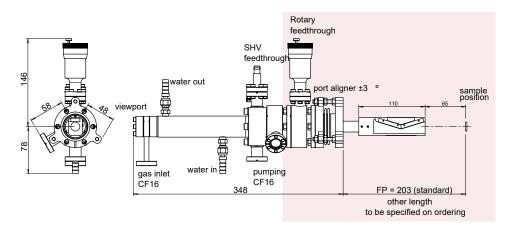
HIS 13 standard VUV source which can be combined with the options listed below. All options can be retrofitted in a factory upgrade at FOCUS GmbH. Please contact us for detailed information. The standard 2-stage differential pumping allows for a system pressure of $10^{-8}-10^{-9}$ mbar during operation for HeI.



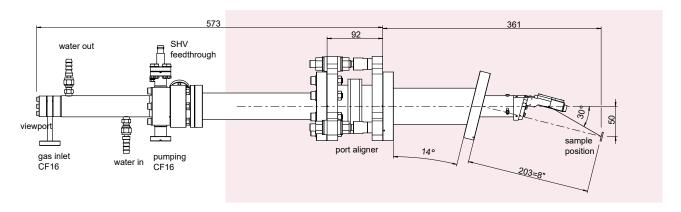
The third pumping stage reduces the pressure to the mid 10⁻¹⁰ mbar range depending on capillary diameter.



Attenuator for HIS 13/14 for VUV-sensitive samples. Even though most application in photo electron spectroscopy aim for maximum intensity there are opposite requirements when working on VUV-sensitive samples as for example organic materials. The Attenuator for HIS 13/14 allows for a variable reduction of photon flux by a factor 10 or 100.

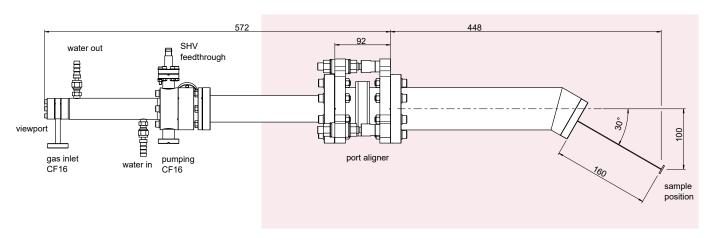


Continously rotatable linear polariser for full exploitation of symmetry selection rules in photoemission. The mirror arrangement provides a 1:1 projection of the capillary opening.



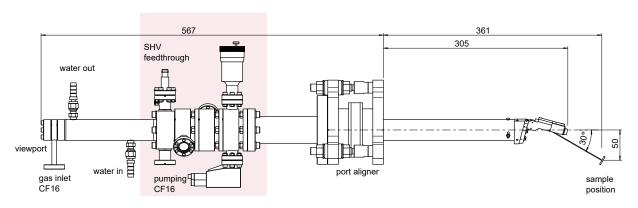
HIS 14 HD dimensions including adapter to meet a 8" flange-to-sample distance. The spot size on the sample depends on the chosen capillary (see table on last page).

HIS 14 HD 200



The HIS 14 HD 200 and HD 250 are designed for an extra large working distance of up to 220mm. They also allow for a NW40CF mounting flange as shown in the drawing.

HIS 14 HD Ar-MONO



The HIS 14 HD Ar-Mono provides an easy tool for obtaining monochromatized VUV-light from Ar gas. This is realized via a heated LiF window that can also be shifted out of the optical path to work with other gases.

SPECIFICATIONS

HIS series						
Useful gas discharge lines:	He I/II, Ne I/II, Kr I/II, Xe I/II, Η (Lyα, Lyβ)					
Photon line width	< 2 meV (He I radiation)					
Pumping	2-, 3- or 4- stage differential pumping					
Operating pressure	Down to 10 ⁻¹¹ mbar range (depends on pump configuration)					
Adjustment & Discharge control	Via backside viewport					
Cooling:	Water cooling					
Bake out temperature:	Up to 250°C					
Plasma Ignition:	Automatic					
Capillary (mm):	0.8/1.2/1.7 (standard)					
Configuration dependent specifications HIS 13 HIS 14 HIS 14 HD HIS 14 HD 200						
	1	MONO	HD 100	MONO	200	MONO
Photon density HeI (HeII) ph/s/mm²	> 2.0·10 ¹¹ * (4.0·10 ¹¹)	> 2.0·10 ¹⁰ * (4·10 ⁰⁹)	> 8.0·10 ¹² (1.6·10 ¹¹)	$> 1.0 \cdot 10^{12}$ $(2.0 \cdot 10^{11})$	$> 2.0 \cdot 10^{12}$ $(4.0 \cdot 10^{11})$	> 2.5·10 ¹¹ (5.0·10 ¹⁰)
Light spot diameter:	working distance depending	working distance depending	< 180 μm (capillary dependent)		< 360 μm (capillary dependent)	
Insertion depth:	Customized (to be defined)					
Photon density ratio:	_		> 50 times		> 12.5 times	
	unfocuse	d source	compared to an unfocused source			
Working distance	typ. 50 - 100 mm		ca. 70 mm		ca. 170 mm	
Mounting flange	CF 40	CF40	CF 63 or CF100	CF63 or CF100	CF 40	CF40

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* For working distance of 70 mm. Higher flux for smaller distances.

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